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APC\Platform 2.0 (release candidate available) **helps automate company-wide improvements**

Villach, Austria, January, 9th, 2006– CenterPoint's [APC\Platform](#) Version 2.0 (release candidate available) helps automate company-wide process improvement efforts by including features like advanced [data mining](#) and [automatic learning](#).

The software is currently successfully evaluated at customers in the semiconductor and steel industries after successful evaluation projects. [APC\Platform 2.0](#) is almost completely redeveloped, integrating new features and several products that were previously separate. It is built on a totally new, service oriented architecture.

APC\Platform focuses on the technically challenging market of fab-wide process monitoring and control. Today's APC applications (classical [run-to-run control](#)) are applied to single process steps, and have very limited capabilities for process improvement.

Integrated data mining and automated learning

The APC\Platform 2.0 is both a platform and a solution for fab-wide gathering from online- and offline-data sources. Off-the shelf [integrated data mining](#) allows Release 2.0 to be used 'from scratch' for certain monitoring and control applications, and with advanced features like [automated learning](#) of associations between global process data.

An inference engine has been integrated, and has significantly improved data acquisition, data processing and data analysis. It enables process engineers to add new [automated decision making](#) rules interactively.

Role-based users

User interaction developed with process engineers ensures the system is user friendly. Clear **role-based user** permissions allow operators, engineers and support IT-administrators to work in an interactive environment. The integrated **interactive workbench** helps develop custom process monitoring and process control scenarios without programming.

From development work, the [APC\Platform](#) allows automated process improvement for elaborating process changes, collaboratively developing new scenarios in a distributed environment, and deploying experimental results to the process environment (optionally integrated with third-party workflow systems).

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Service oriented distributed architecture

The APC\Platform 2.0 is built on a [service oriented distributed architecture](#). This approach makes installations

- o **scaleable** and thus growing with the increasing number of applied scenarios,
- o and **technically open** to be integrated with already existing applications (e.g. Manufacturing Executive Systems, processing equipment, metrology tools and measurement systems, data bases).

Industry standards like **OPC XML** and the new **SEMI EDA** standards are an integrated part of the product.

The APC\Platform 2.0 is also the fab-wide EDA client of the semiconductor industry also applying the [EDA standards](#) within diagnostics, monitoring and control scenarios.

Ask at sales@centerpoint.eu.com for more details about the new release and further development steps. Be part of a common vision to face new challenges in high technology manufacturing.

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